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Patent  
Attorney's Docket No. 015290-238

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

Jeffrey HUNG et al.

Application No.: 09/002,007

Filed: December 31, 1997

For: ETCHING PROCESS FOR ORGANIC  
ANTI-REFLECTIVE COATING



) Group Art Unit: 1765

) Examiner: L. Vinh

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**AMENDMENT**

**BOX AF**  
Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the final Official Action dated January 13, 2000, the period for response having been extended until May 13, 2000, please amend the above-identified application as follows.

**IN THE CLAIMS:**

Please cancel Claims 14 and 15 without prejudice or disclaimer of the subject matter thereof and amend Claims 1 and 3 as follows:

1. (Twice Amended) A process for removing exposed areas of an organic ARC on a metallic layer, the exposed areas of the ARC having been exposed by previously etching a photoresist covering the ARC, the process comprising exposing the exposed areas of the ARC to an oxygen-free system of etching agents in an ionized state in a reaction chamber

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